

Title (en)

PROCESS FOR THE ZINC-CALCIUM PHOSPHATIZING OF METAL SURFACES AT A LOW TREATING TEMPERATURE

Publication

EP 0155547 B1 19881207 (DE)

Application

EP 85102057 A 19850225

Priority

DE 3407513 A 19840301

Abstract (en)

[origin: ES8602963A1] Metal surfaces are phosphated with an acidic phosphating soln. contg. Zn, Ca, phosphate and accelerator and opt. Ni or fluoride. The metal surface, cleaned by degreasing, is contacted, without activation, at 30-65 (48-57) deg. C. with solns. contg. (a) over 0.5-1.5 g/l Ca ions, (b) 0.5-1.5 g/l An ions, (c) 10-50 g/l PO₄ ions, and, as accelerator, (d) 0.5-30 g/l NO₃ ions and/or 0.01-0.6 g/l NO₂ ions and/or 0.2-10 g/l ClO₃ ions and/or 0.1-2 g/l organic nitro cpd. and/or 0.01-0.5 g/l inorganic peroxide, esp. H₂O₂. - The solns. have pH 2.2-3.8. The molar ratio of free acid to total acid is 1 : 10 to 1 : 60 Wt. ratio (Ca ions + Zn ions) :PO₄ ions is 1 : over 8 to 1 : 40.

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IPC 8 full level

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CPC (source: EP US)

C23C 22/22 (2013.01 - EP US); **C23C 22/36** (2013.01 - EP US); **C23C 22/367** (2013.01 - EP US)

Citation (examination)

- DE 1521818 A1 19691016 - LUBRIZOL CORP
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